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Antimonide-based optoelectronic devices epitaxially grown on Silicon

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Acknowledgment

- L. Cerutti, J.-B. Rodriguez, J.-P. Perez, P. Christol, R. Teissier, A.N. Baranov
- A. Castellano, K. Madiomanana, L. Monge Bartolome, H. Nguyen-Van, M. Rio Calvo, J.R. Reboul: PhD students
- G. Boissier, G. Narcy: technical staff
- M. Niehle, A. Trampert, PDI Berlin: TEM
- L. Largeau, G. Patriarche, C2N, U. Paris-Saclay: TEM
- T. Cerba, T. Baron, CNRS/CEA Grenoble: MOVPE templates
- Funding from:
 - French program on “Investments for the future” (*EquipEX*)
 - French national research agency (*ANR*)
 - European Union H2020



OUTLINE

- Antimonide opto devices on Si: motivations
- III-Vs on Si: issues
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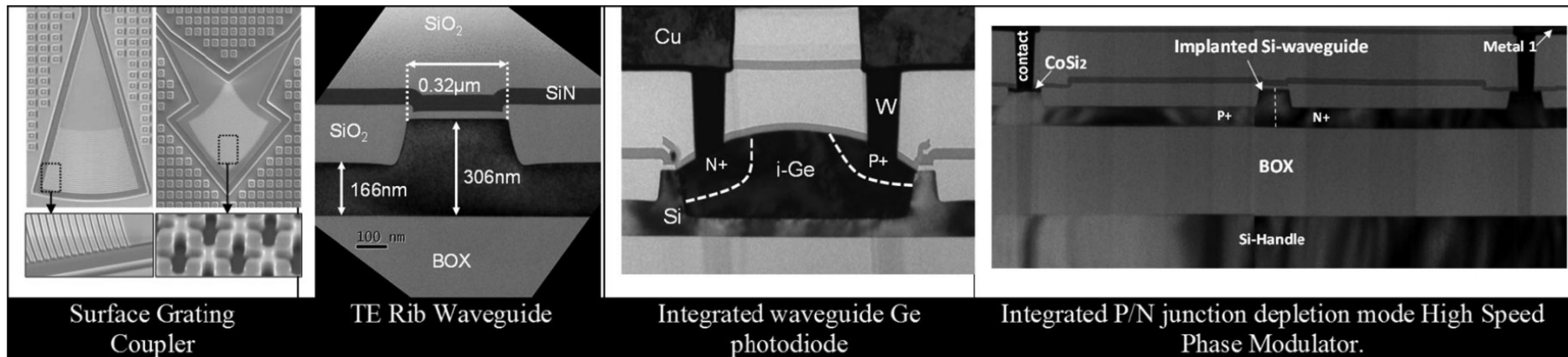
Silicon Photonics R&D and Manufacturing on 300-mm Wafer Platform

F. Boeuf *et al.* (ST Microelectronics)

JOURNAL OF LIGHTWAVE TECHNOLOGY, VOL. 34, NO. 2, JANUARY 15, 2016

Si photonics

A complete toolbox!



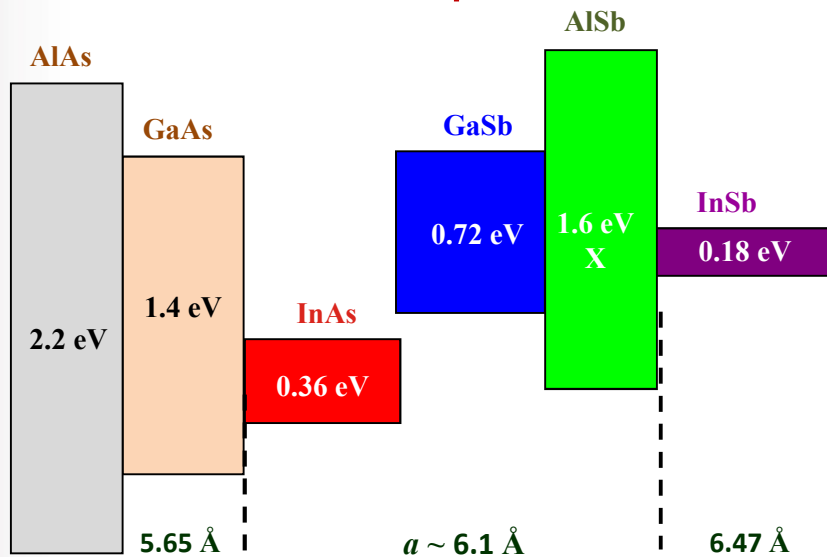
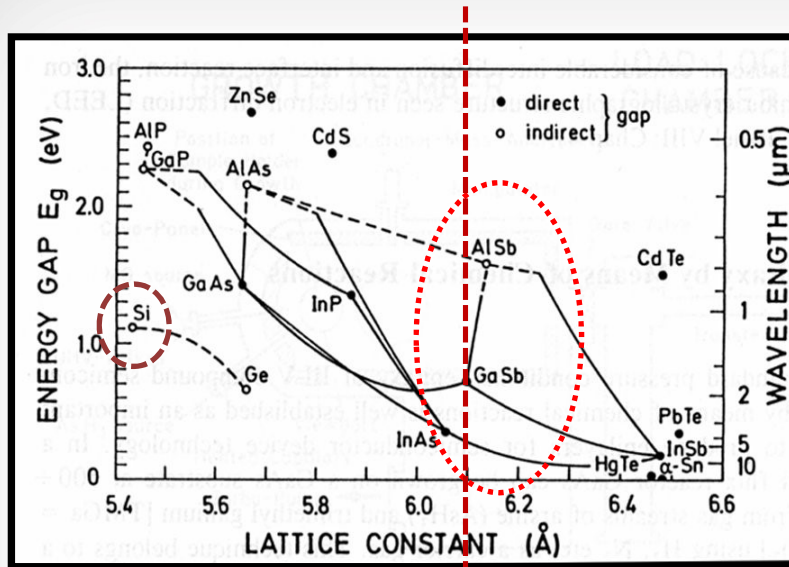
Almost complete: the laser is still missing!

Si and Ge are indirect bandgap materials: no light emission

Si-photonics needs III-V semiconductor materials

Antimonide compound semiconductors

GaSb, AlSb, InSb, InAs and their alloys



- Large bandgap range:
0.1 – 1.8 eV
- Various band alignments:
Type I, Type II, Type III
- Large band offsets:
 $\Delta E_c = 0 - 2 \text{ eV}$
 $\Delta E_v = 0 - 0.5 \text{ eV}$

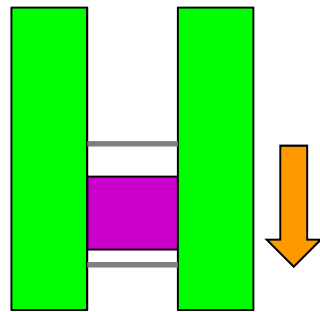
➡ *Unrivalled band structure engineering*

➡ *Mismatch with Si $\sim 12\%$*

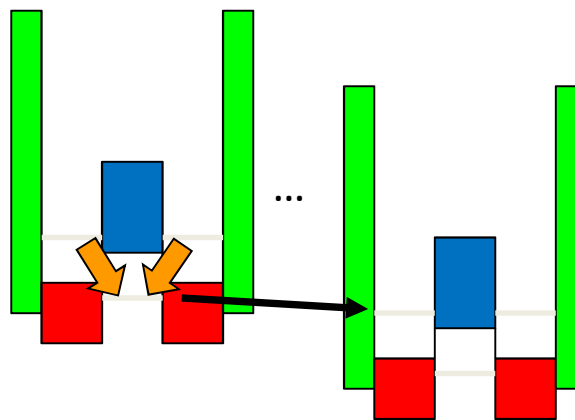
III-Sbs: perfectly suited for the IR wavelength range

Sb-based IR devices

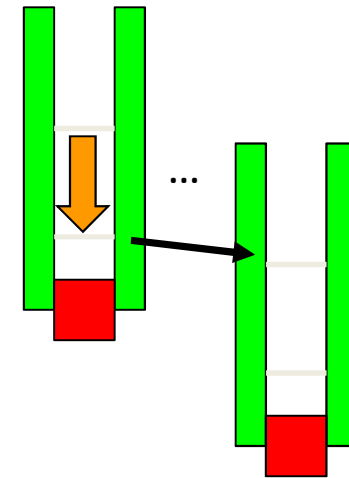
QW Lasers
GaInAsSb/AlAsSb



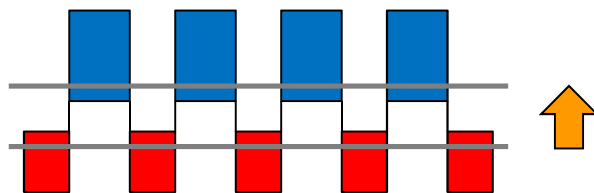
Interband Cascade Lasers
InAs/GaSb/AlSb



Quantum Cascade Lasers
InAs/AlSb

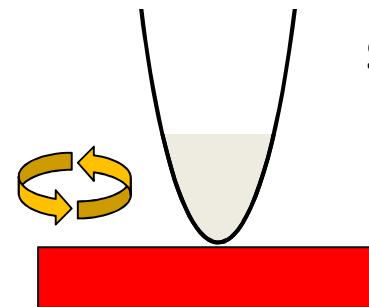


Type II SL Detectors
InAs/GaSb (or InAs/InAsSb)

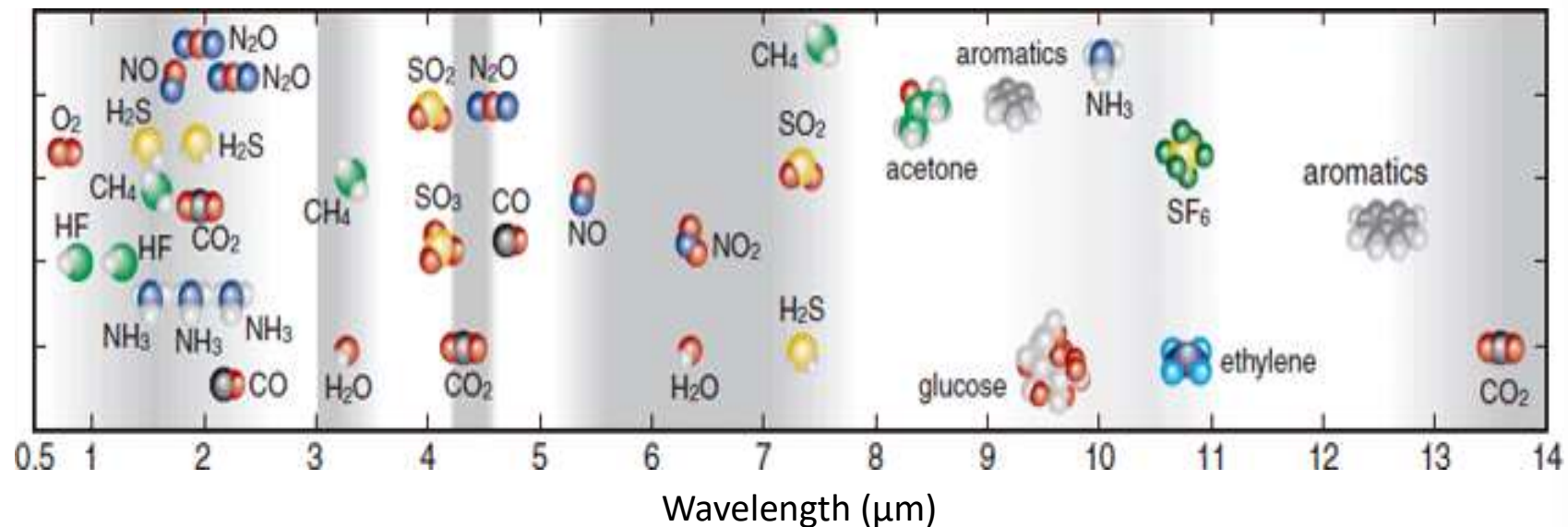


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SC Plasmonics
InAs(Sb)



The sensing challenge



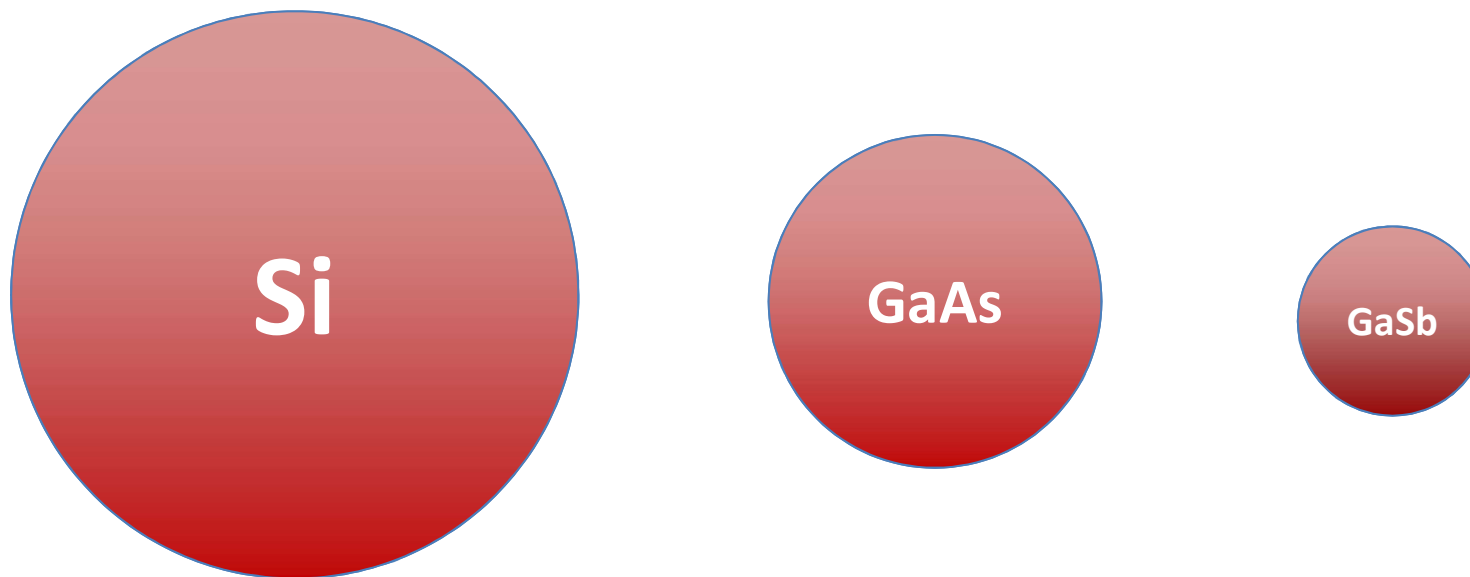
Mid-IR: atmosphere transparency windows + “fingerprint” region

A wealth of applications

Atmospheric pollution monitoring, industrial process control, food industry, health, security, free space optics, etc.

Increasing demand for low-cost, small footprint, smart, photonic sensors.

The substrate challenge



	Si	GaAs	InP	GaSb
Diameter (mm)	300	175	100	100
\$/cm ²	0.5	2	6	12

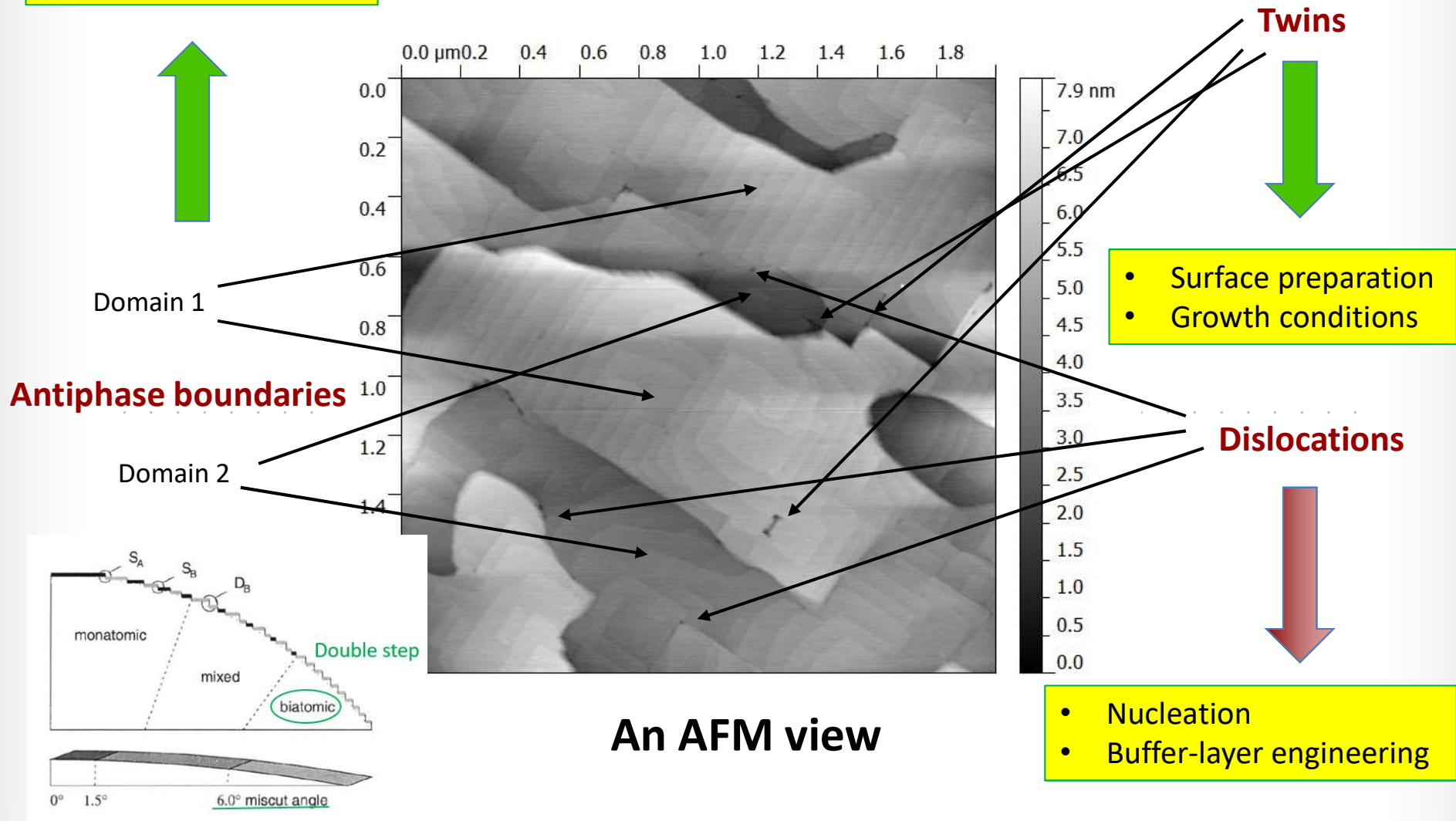
Low cost mid-IR devices → Si platform.

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III-V epitaxy on Si: a number of mismatches

- Surface preparation
- Off-cut substrates



Dislocations **cannot be avoided**, but their threading density can be reduced

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Si substrates

- 4 – 6° offcut (001) 2 inch. Si substrates

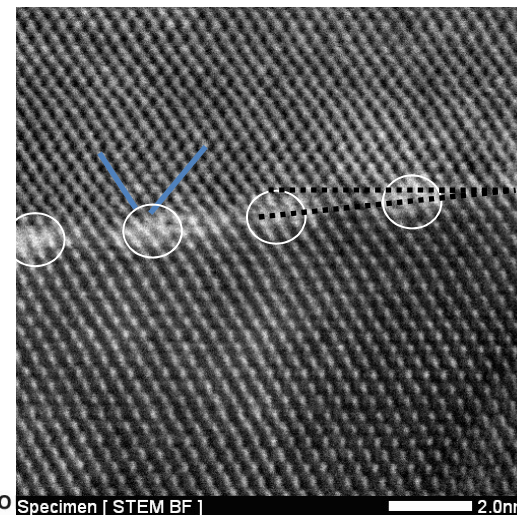
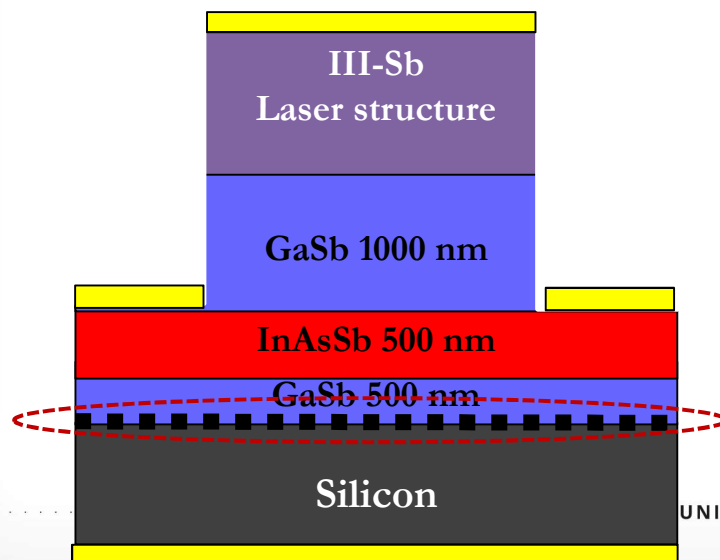
Standard III-V molecular-beam epitaxy (MBE) reactor

- Solid-source MBE with load-lock chamber
- Valved-cracker cells for As and Sb
- Standard group-III effusion cells
- $T_{\text{substrate}} < 850\text{ }^{\circ}\text{C}$

- Growth chamber and $T_{\text{substrate}}$ not compatible with *in-situ* Silicon de-oxidation
- No Si buffer-layer growth in (most) III-V systems

GaSb on Si templates

- 4 – 6° off (001)Si
- *Ex-situ* O₂ Plasma + HF Si preparation cycles
- *In-situ* annealing at 800°C
- 4 MLs AlSb @ 450°C
- 500 nm GaSb buffer layer
- 500 nm InAsSb bottom contact layer
- ~ 1 μm GaSb buffer layer

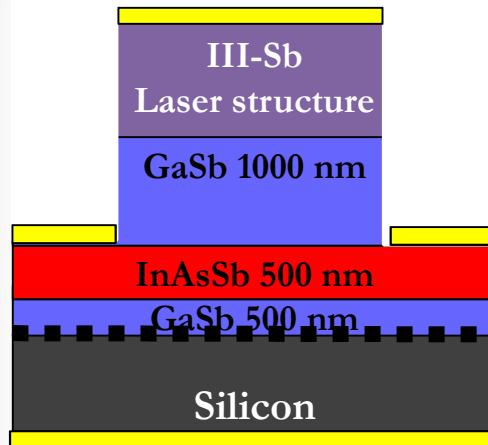


TEM image: A. Trampert, PDI-Berlin

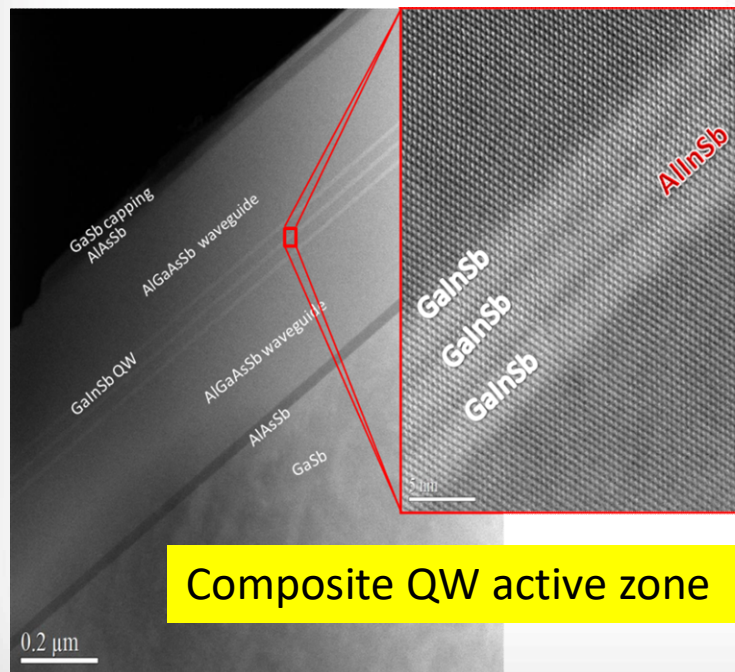
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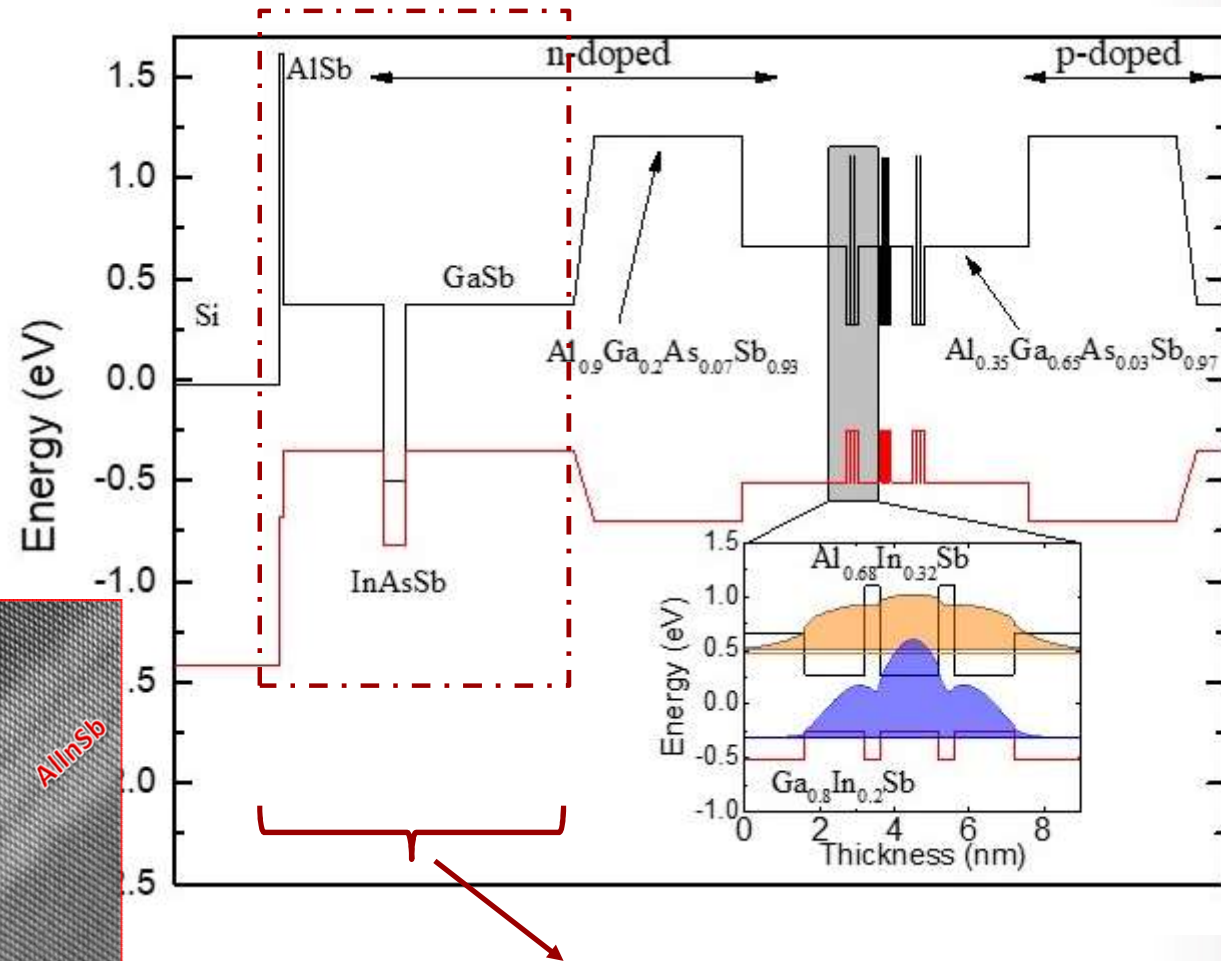
1.55- μm GaSb laser on Si substrate



TEM: G. Patriarche, CNRS

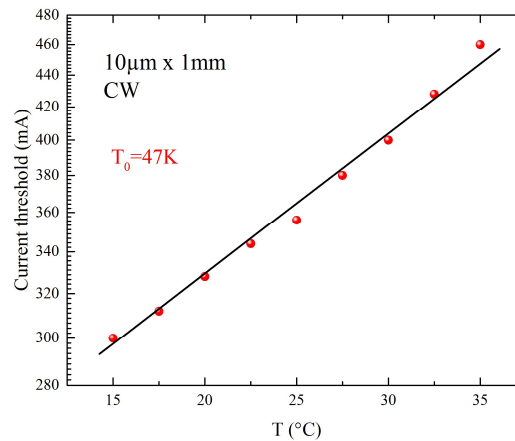
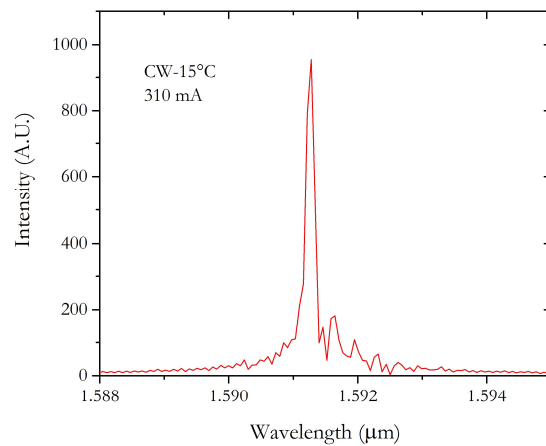
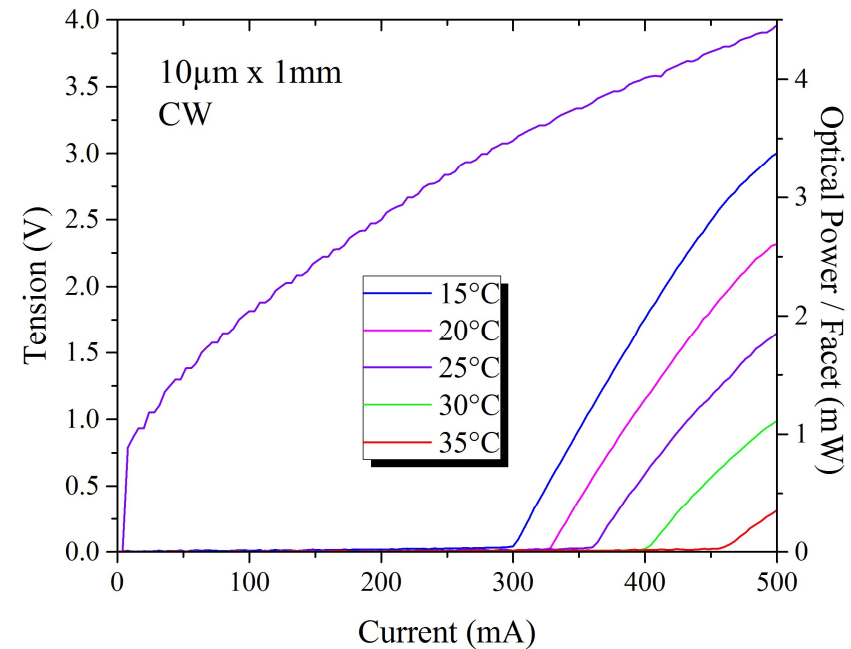
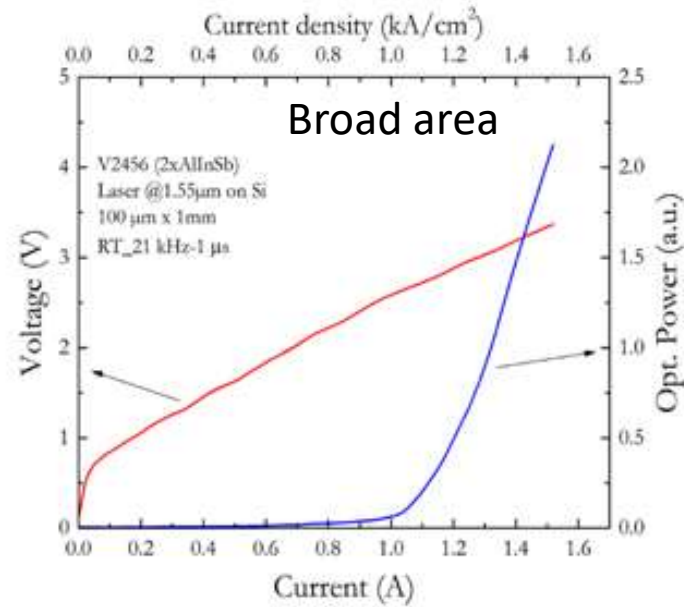


Composite QW active zone



GaSb-based template

1.55- μm GaSb laser diode on Si substrate

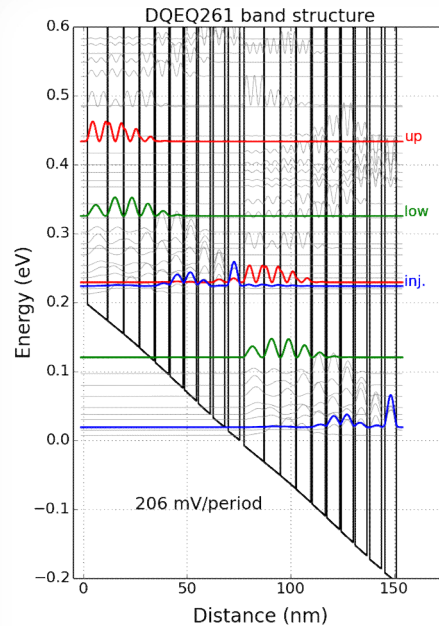


- $\lambda \sim 1.59 \mu\text{m}$
- CW operation up to 35 $^{\circ}\text{C}$
- $P_{\text{out}} > 3\text{mW}$ @ 15 $^{\circ}\text{C}$
- $T_0 \sim 47 \text{ K}$
- $J_{\text{th}}(\text{Si}) \sim 3\text{-}5 \times J_{\text{th}}(\text{GaSb})$

OUTLINE

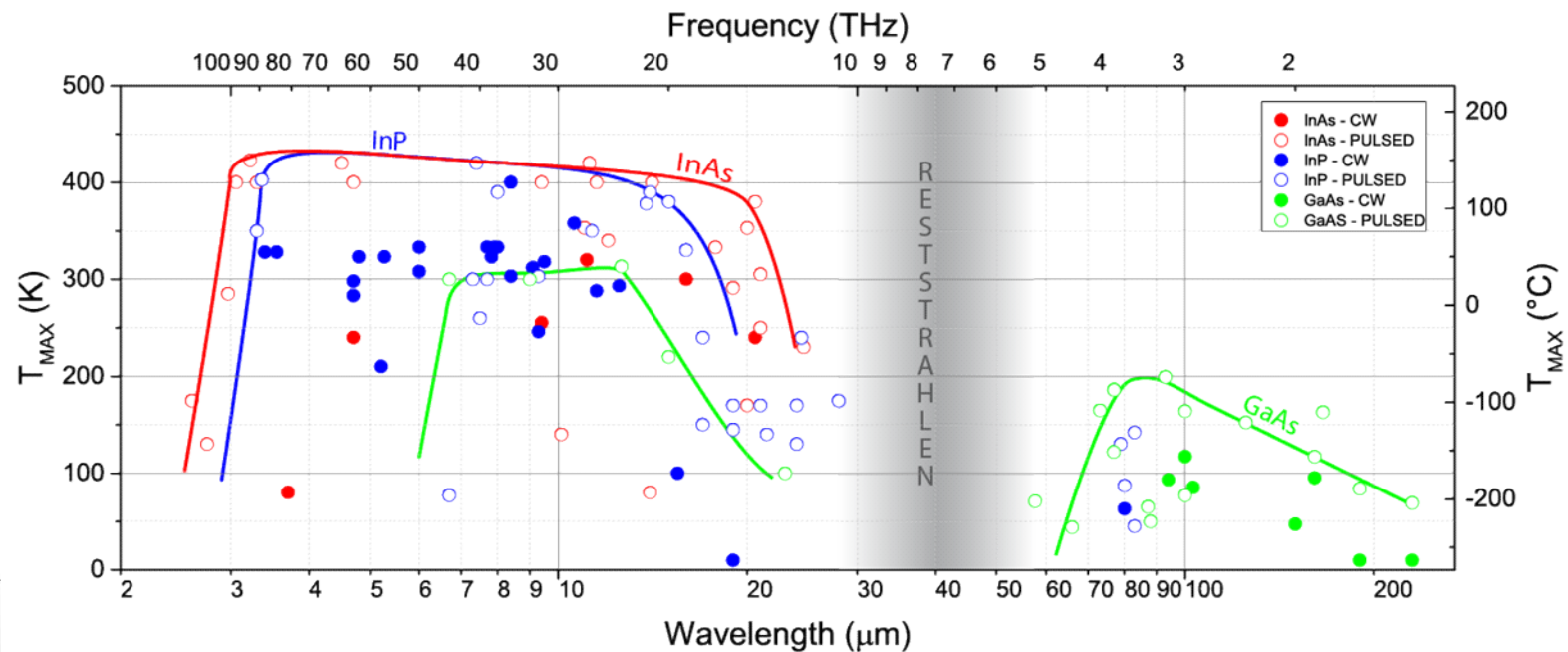
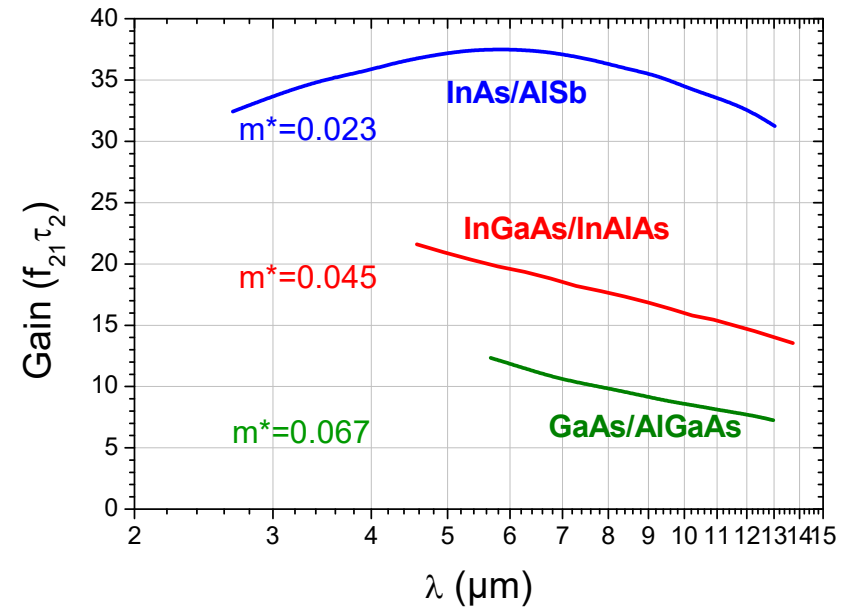
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InAs/AlSb: very good intrinsic properties for QCLs

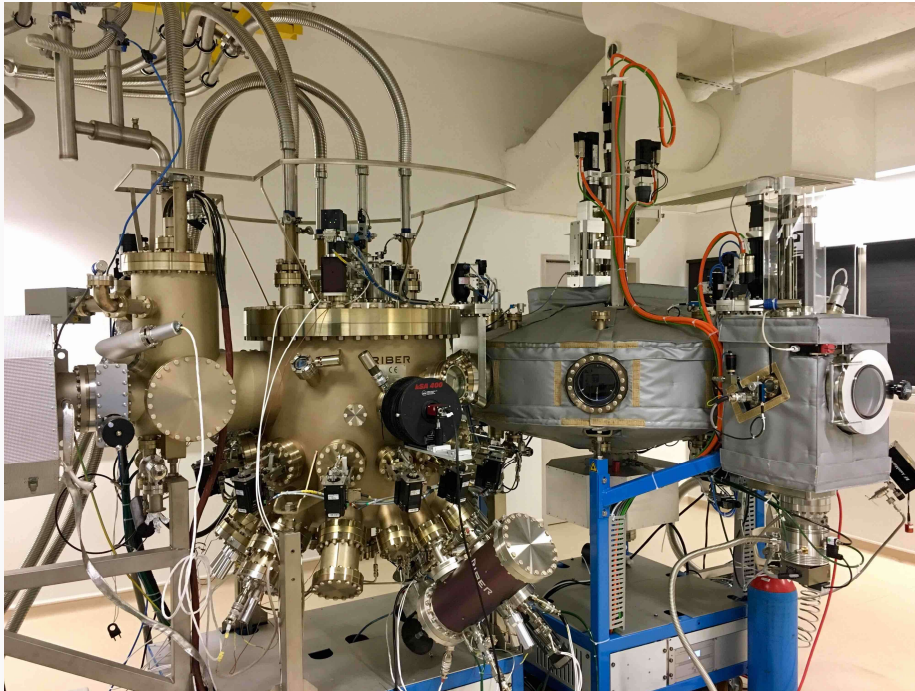


Gain in QCL

$$g \propto \frac{1}{m^*{}^{3/2}}$$



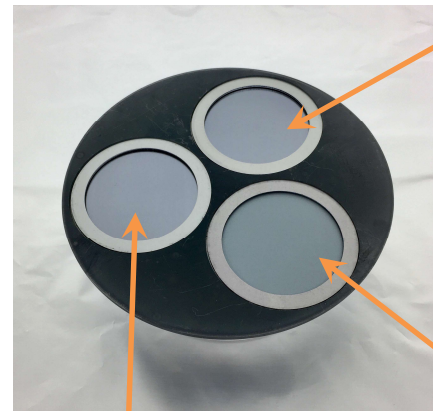
MBE growth



RIBER 412 MBE system

Substrate 2"n-InAs (100)

InAs



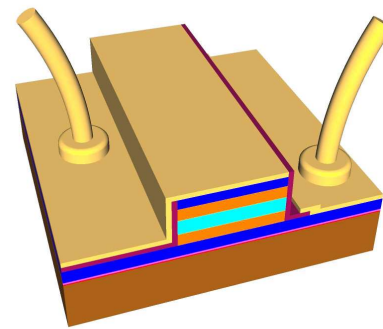
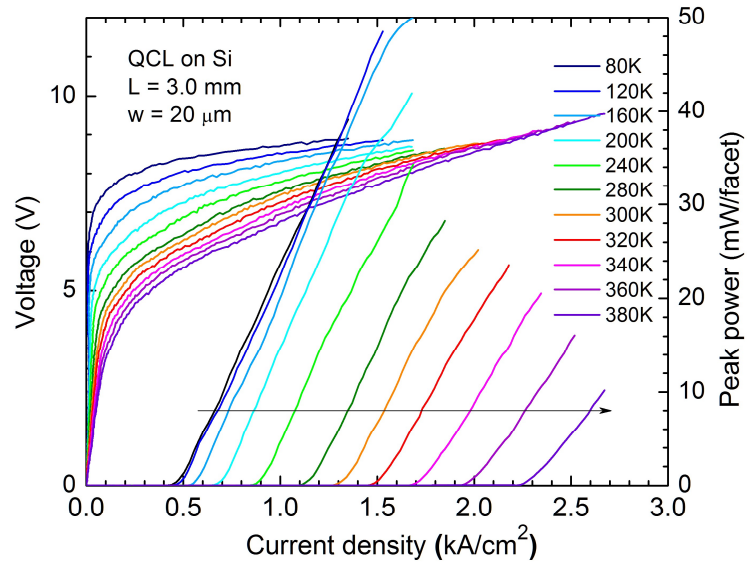
Dummy

Template on 2" Si (100) 6°off

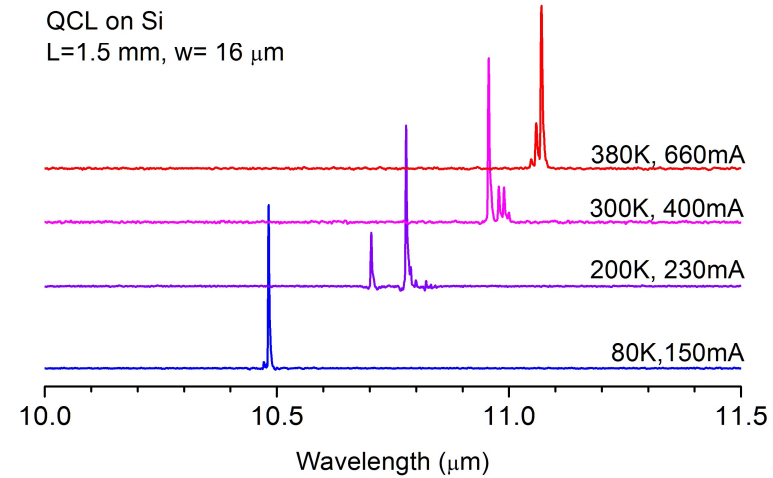
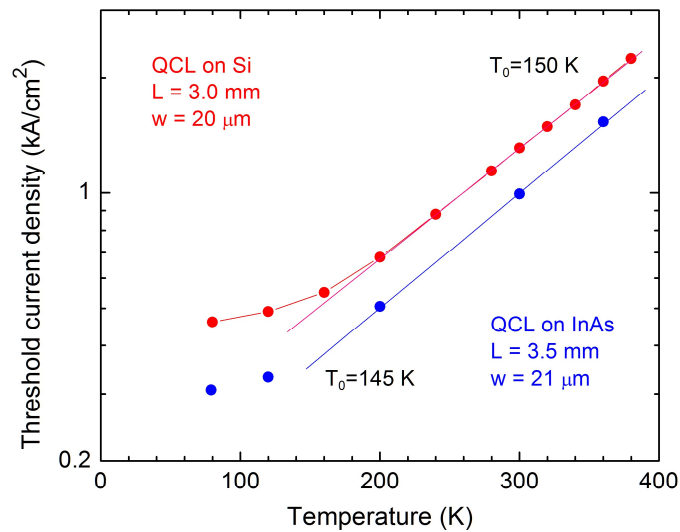
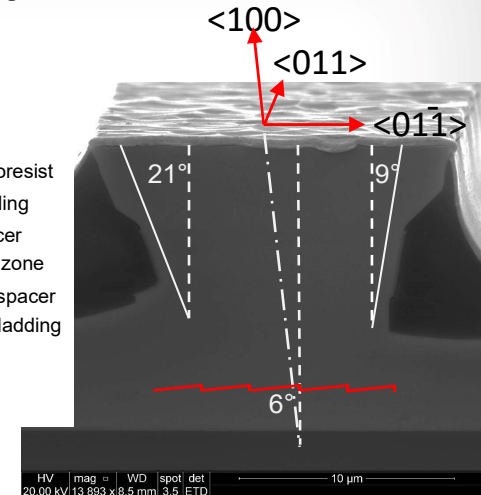
Side-by-side growth on 2 substrates

InAs 0.2 μm
GaSb 1 μm
AlSb 4 ML
Si (100) 6°off

InAs/AlSb QCL on Si



- Au contacts
- hard baked photoresist
- n⁺-InAs top cladding
- nid-InAs top spacer
- InAs/AlSb active zone
- nid-InAs bottom spacer
- n⁺-InAs bottom cladding
- GaSb template
- Si substrate



First-ever report of a QCL grown on Si
Similar performances on Si and on InAs substrates

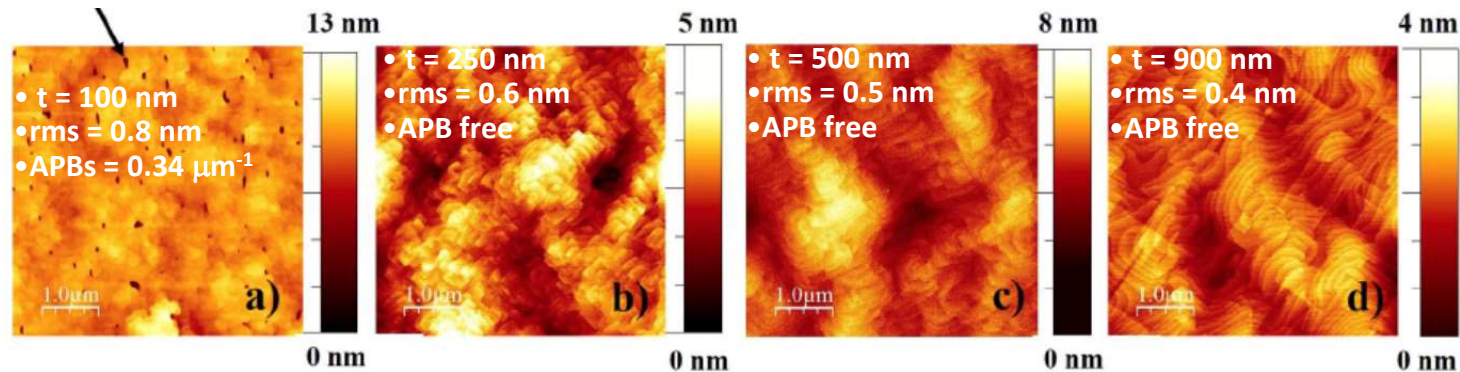
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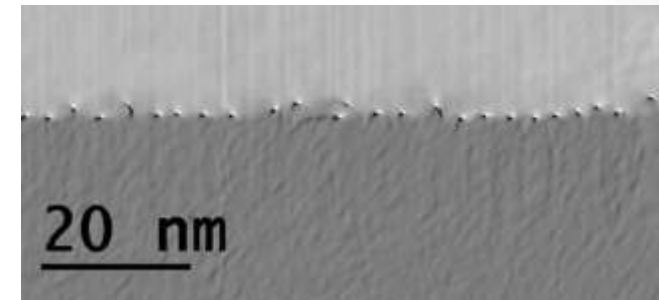
GaSb template grown on on-axis Si by MOVPE

Remote plasma de-oxydation + high temperature annealing under H₂ flow
in a Si cluster-tool

→ *Growth of smooth GaSb epilayers on 300 mm on-axis (001)-Si substrate*



- 0.11° miscut (001)-Si 300 mm substrate
- Low temperature nucleation layer (450 C)
- High temperature GaSb epilayer



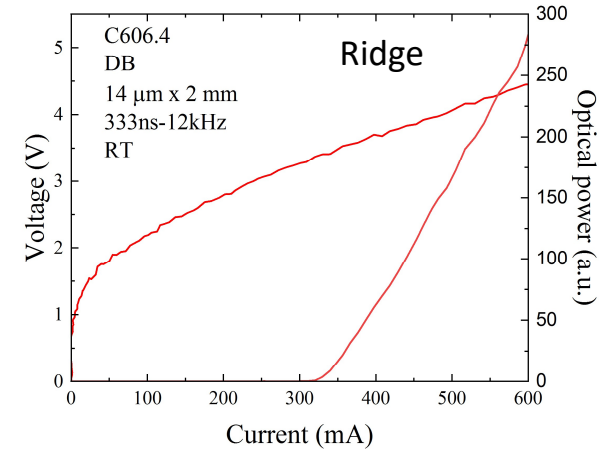
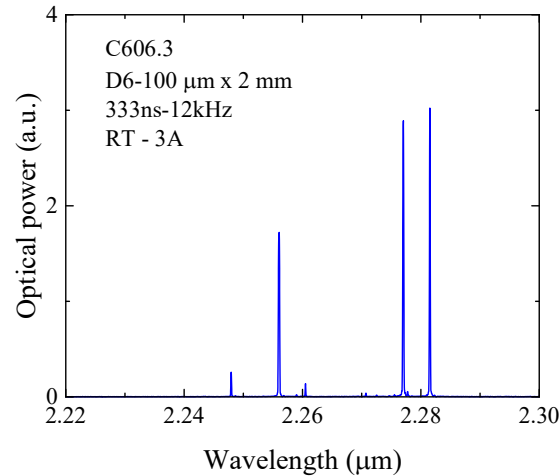
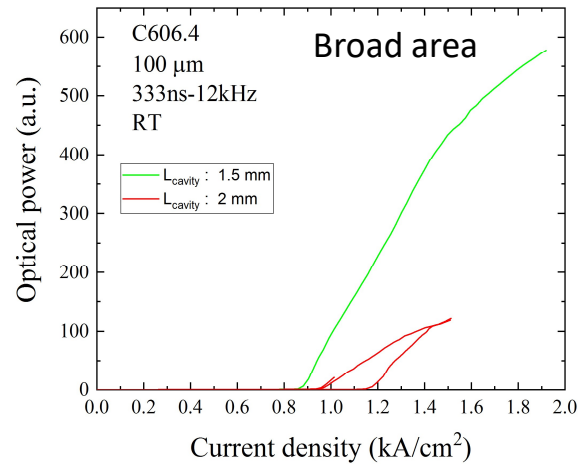
• 90° dislocations array at the interface

T. Cerba *et al.*, Thin Solid Films 645 (2018) 5 (LTM, CNRS, CEA, University Grenoble Alpes)

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2.3- μm GaSb laser on MOVPE-GaSb/Si template



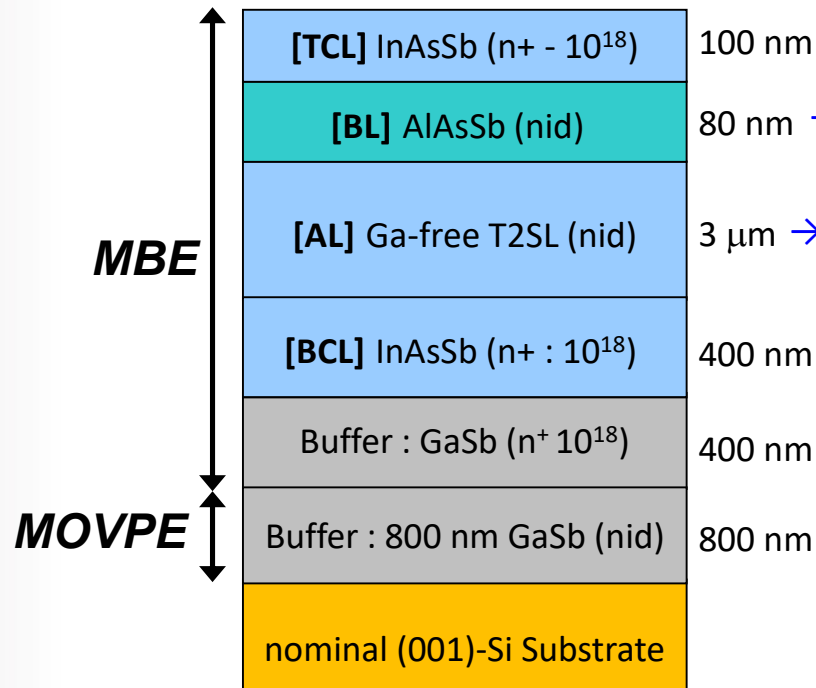
- Broad Area laser: $J_{\text{th}} = 0.9 \text{ A}/\text{cm}^2$ (1.5 mm) – 1.2 kA/cm^2 (2 mm)
- Ridge (14 μm) laser: $I_{\text{th}} = 325 \text{ mA}$ under **pulsed operation**

No cw operation (yet)
Lower performances than on 6°off MBE templates
Under investigation!

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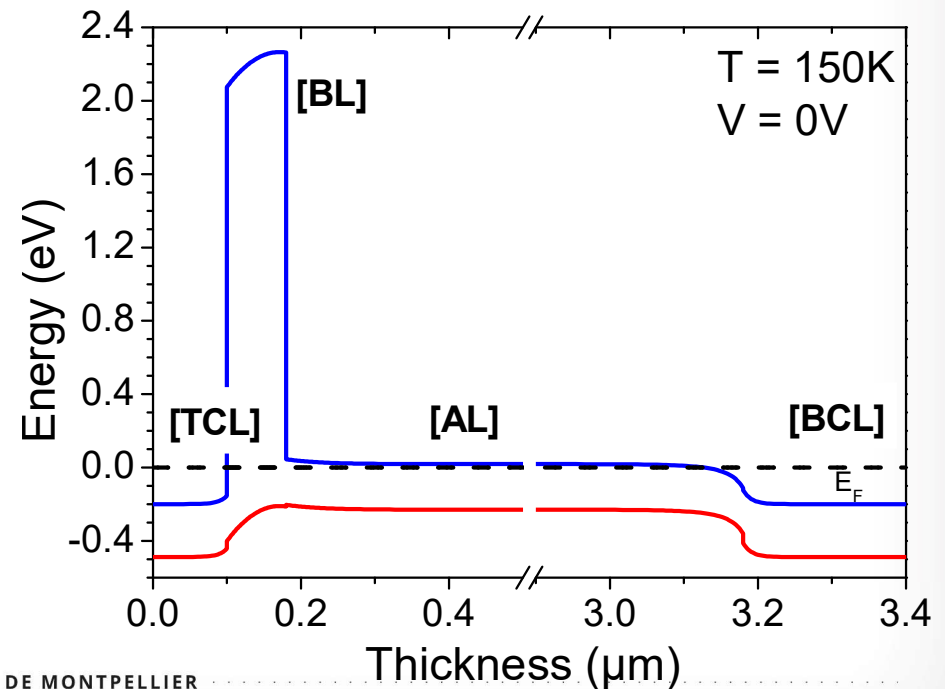
InAs/InAsSb type-II superlattice photodetector on MOVPE GaSb template



Stacking of the MWIR Ga-free T2SL barrier detector

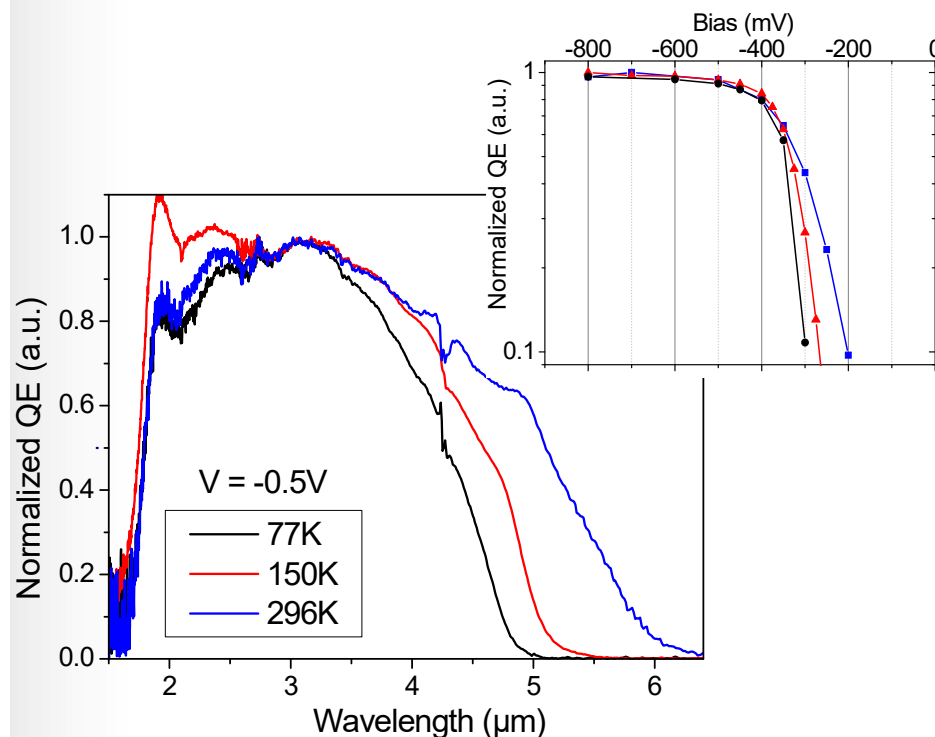
Band diagram @ 150 K and 0 V using ATLAS SILVACO

- VBO ~ 10 meV between AL and BL
- thin depletion layer in the AL (AL: n -type, BL: p -type)



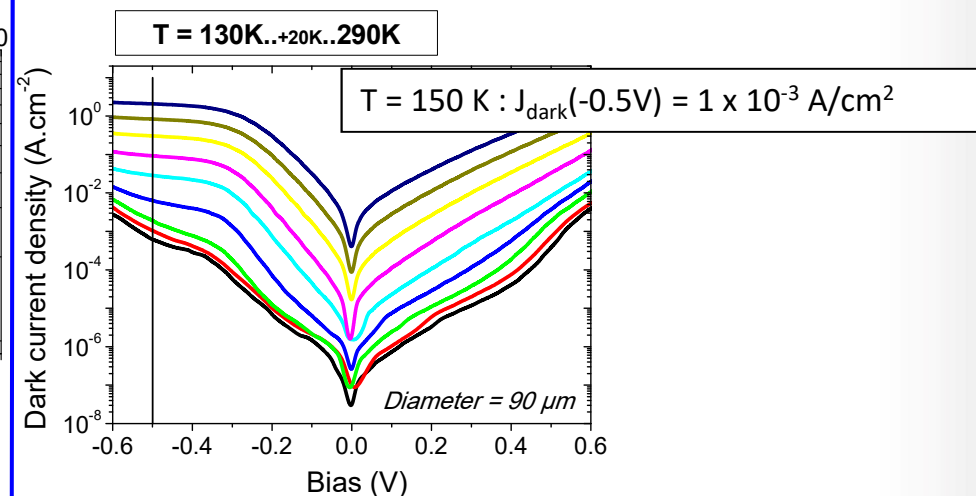
Results

*Spectral responses :
(normalized @ 3 μm)*

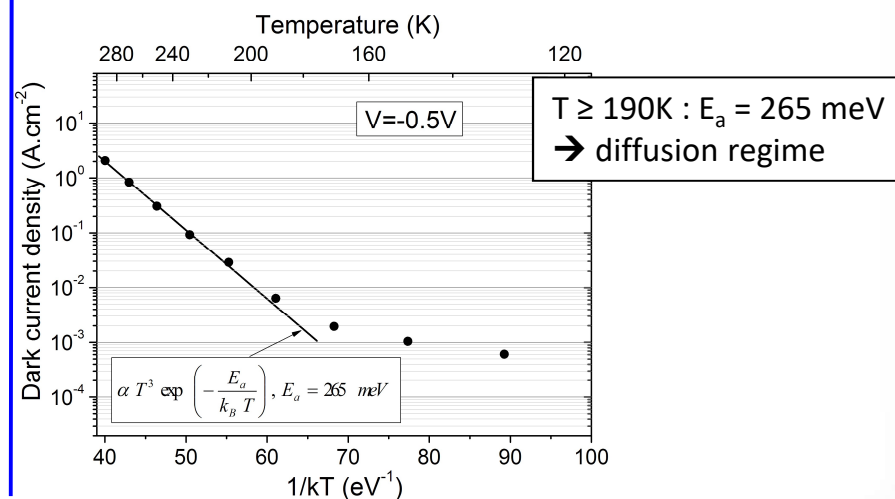


- QE saturates at $V_{\text{bias}} = -0.5\text{V}$
- $\lambda_{\text{co}} = 4.7 \mu\text{m}$ @ 150 K
- calibrated QE to be measured

Dark current density :



Arrhenius graph @ $V_{\text{bias}} = -0.5\text{V}$



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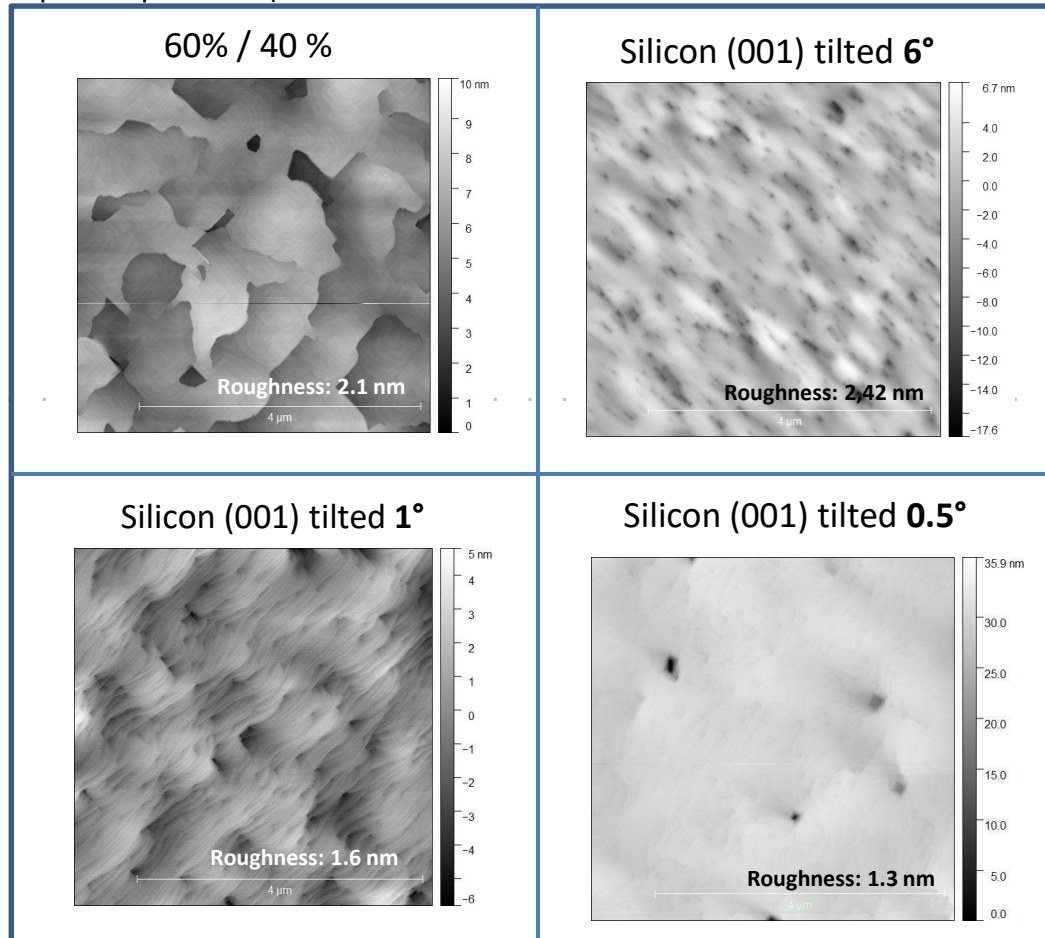
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Toward on-axis Si: an AFM view

Improved Si-surface preparation and growth start

500 nm GaSb on Si

5 μm x 5 μm AFM pictures



APD free down to 0.5° miscut

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GaSb-based lasers on Si: summary

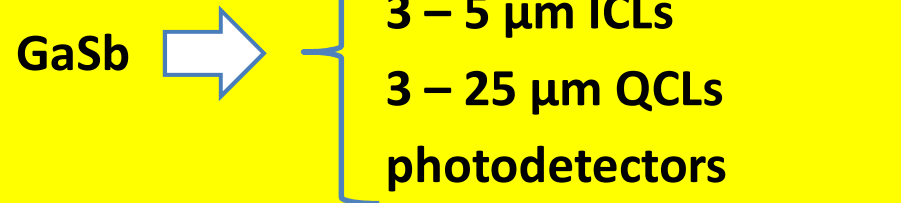
- Laser diodes grown on *off-cut* Si substrates
 - ➡ CW laser operation between 1.5 and 2.X μm
 - ➡ $T_{\text{max}} > 35\text{ }^{\circ}\text{C}$, $T_0 \sim 50\text{ K}$, $P_{\text{max}} = 3 - 10\text{ mW/uncoated facet}$
 - ➡ $J_{\text{th}}(\text{Si}) \sim 3 - 5 \times J_{\text{th}}(\text{GaSb})$
- First-ever demonstration of QCL grown on *off-cut* Si substrates
 - ➡ InAs/AlSb QCL design (vertical transition) for $\lambda \sim 11\text{ }\mu\text{m}$
 - ➡ Similar performances on Si and InAs substrates
- Preliminary results on *on-axis* Si substrates (MOVPE template)
 - ➡ Pulsed operation of lasers diodes
 - ➡ InAs/InAsSb type-II superlattice photodetectors
- Anti-phase-domain free GaSb MBE-templates

GaSb-based lasers on Si: what's next?

- Devices on on-axis MBE templates
- Dislocation filtering
- Optimized device design and technology

Future

A complete IR optoelectronics toolbox integrated on Silicon



Development of a variety of Mid-IR integrated sensors